

SILICON-CONTAINING COMPOSITIONS FOR SPIN-ON ARC/HARDMASK MATERIALS

ABSTRACT OF THE DISCLOSURE

Antireflective compositions characterized by the presence of an Si-containing polymer having pendant chromophore moieties are useful antireflective coating/hardmask compositions in lithographic processes. These compositions provide outstanding optical, mechanical and etch selectivity properties while being applicable using spin-on application techniques. The compositions are especially useful in lithographic processes used to configure underlying material layers on a substrate, especially metal or semiconductor layers.